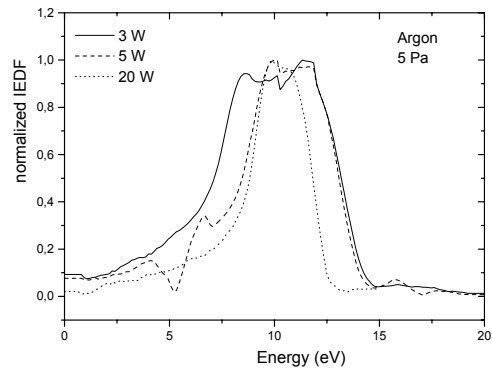


## 13.56 MHz Inductively Coupled Plasma Source ICP-P 200

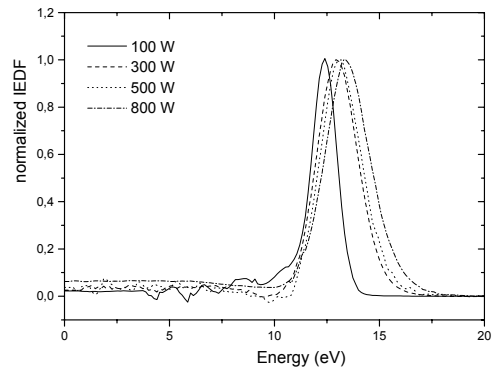


### Typical Data

These data were taken for typical vacuum chamber geometry at minimum reflected power. Depending on the installation and set-up used the data may vary.



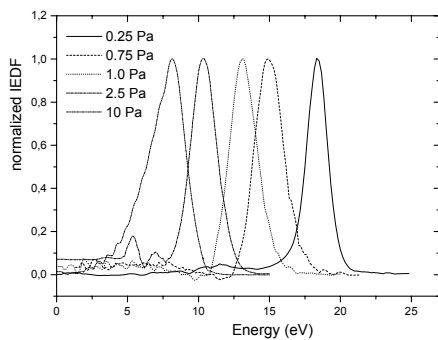
(2a)



(2b)

### Ion Energy Distribution Functions

The Argon and Nitrogen ion energy distribution functions (IEDF) were measured by a retarding field analyzer (RFA) which was flanged on the grounded wall of the plasma chamber. It can be seen from Fig. 1 and 2 that the maximum ion energy is below 20 eV for all pressures and powers investigated.



**Fig. 1 Ion energy distribution in a nitrogen plasma as a function of pressure**

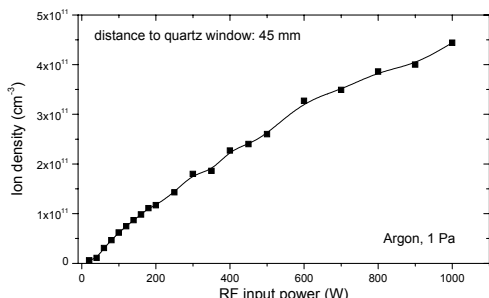
The mean ion energy is increases with decreasing pressure and is determined essentially by the dc plasma potential. (Rf power 500 W, 10 sccm nitrogen gas flow).

**Fig. 2 Ion energy distribution in an argon plasma as a function of rf power**

At low rf power a broader distribution is observed due to the capacitive coupling is observed while above 20 W the discharge operates in the inductive mode even without a Faraday shield (Fig. 2a: 5 Pa, Fig. 2b: 1 Pa Ar; gas flow 10 sccm).

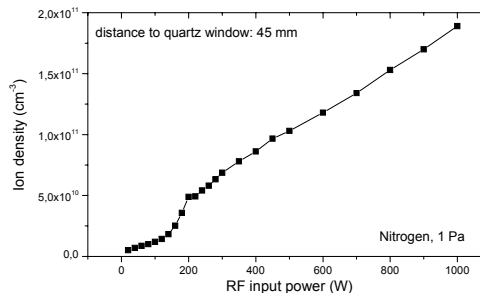
## Plasma density

The Argon and Nitrogen ion density, measured by a double Langmuir probe system also manufactured by JE PlasmaConsult GmbH, downstream the quartz window is shown in Figs. 3 to 7.



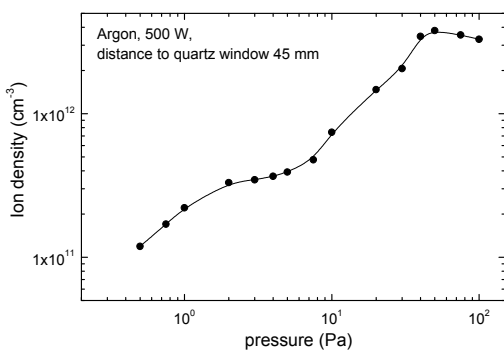
**Fig. 3 Plasma density in an Ar-plasma as a function of rf-power**

The density can be varied over 2 orders of magnitude and exceeds  $3 \times 10^{11} \text{ cm}^{-3}$  at rf-powers  $> 400 \text{ W}$  (position 45 mm downstream, 1 Pa Ar, gas flow 10 sccm).



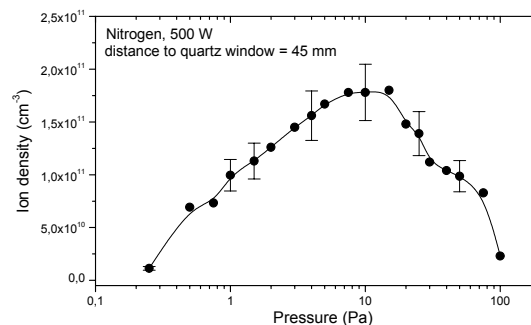
**Fig. 4 Plasma density in an N<sub>2</sub>-plasma as a function of rf-power**

The density can be varied over 2 orders of magnitude and exceeds  $1 \times 10^{11} \text{ cm}^{-3}$  at rf-powers  $> 400 \text{ W}$  (position 45 mm downstream, 1 Pa N<sub>2</sub>, gas flow 10 sccm).



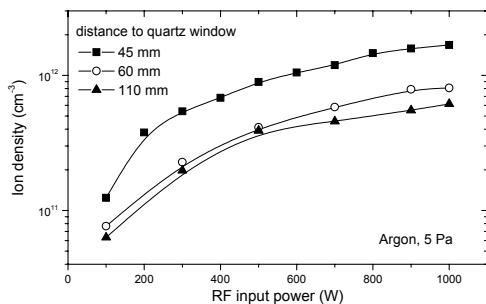
**Fig. 5 Plasma density in an Ar-plasma as a function of pressure**

The *ICP-P 200* can be operated over 2 orders of magnitude of pressure. The plasma density exceeds  $2 \times 10^{11} \text{ cm}^{-3}$  for pressures between 1 and 100 Pa (position 45 mm downstream,  $P_{rf} = 500 \text{ W}$ , gas flow 10 sccm).



**Fig. 6 Plasma density in an N<sub>2</sub>-plasma as a function of pressure**

The *ICP-P 200* can be operated over 2 orders of magnitude of pressure. The plasma density exceeds  $1 \times 10^{11} \text{ cm}^{-3}$  for pressures between 1 and 40 Pa (position 45 mm downstream,  $P_{rf} = 500 \text{ W}$ , gas flow 10 sccm).



**Fig. 7 Plasma density in an Ar-plasma as a function of rf-power for different distances to the quartz window (5 Pa Ar, gas flow 10 sccm)**